L Number	Hits		DB	Time stamp
-	0	"20020157068"	USPAT	2004/05/06 11:19
, <del>-</del>	1	"20020157068"	USPAT;	2004/05/06 15:34
_	1	"05206219"	US-PGPUB	
_	472		JPO	2004/05/06 11:19
	. 4/2	(opc or optical near process near	USPAT;	2004/05/10 18:16
	ĺ	correction) and photolithography and mask	US-PGPUB;	· .
t .			EPO; JPO;	•
			DERWENT;	
	· ·	· ·	IBM TDB	
. –	44	1 ( TE	USPAT;	2004/05/06 16:01
		correction) and photolithography and mask)	US-PGPUB;	
		and hierarchy	EPO; JPO;	
1			DERWENT;	
			IBM TDB	
-	472	(opc or optical near process near	USPAT;	2004/05/06 16:00
1		correction) and photolithography and (mask		2004/05/06 16:00
l. 3		or reticle near writ\$3 near (tool or	US-PGPUB;	
		device)	EPO; JPO;	,
		desire!!	DERWENT;	
		//ana an anti-anti-anti-	IBM_TDB	4
-	44	((opc or optical near process near	USPAT;	2004/05/06 16:03
		correction) and photolithography and (mask	US-PGPUB;	1
*		or reticle near writ\$3 near (tool or	EPO; JPO;	
1		device))) and hierarchy	DERWENT;	
			IBM TDB	
-	22	(((opc or optical near process near	USPAT;	2004/05/10 15:25
		correction) and photolithography and (mask	US-PGPUB;	
*		or reticle near writ\$3 near (tool or	EPO; JPO;	
		device))) and hierarchy) and (reduc\$3 or	DERWENT;	
		decreas\$3 or eliminat\$3) with data	IBM TDB	.00- *
l <del>-</del>	19	(((opc or optical near process near	USPAT;	2004/05/10 15:26
		correction) and photolithography and (mask	JPO;	2004/05/10 15.20
		or reticle near writ\$3 near (tool or	DERWENT	
		device))) and hierarchy) and (reduc\$3 or	DEKWENT	
e e	,	decreas\$3 or eliminat\$3) with data		
	2	((((opc or optical near process near	HCDAM.	2004 (05 /10 15 20
	· .	correction) and photolithography and (mask	USPAT;	2004/05/10 15:30
,		or reticle pear write? / and (mask	JPO;	
		or reticle near writ\$3 near (tool or	DERWENT	
		device))) and hierarchy) and (reduc\$3 or		į
		decreas\$3 or eliminat\$3) with data ) and	•	-
		(cop\$3 or transfer\$3) with cell	Y .	
_	2	((((opc or optical near process near	USPAT;	2004/05/10 15:30
ĺ		correction) and photolithography and (mask	JPO;	
l		or reticle near writ\$3 near (tool or	DERWENT	*
		device))) and hierarchy) and (reduc\$3 or		
		decreas\$3 or eliminat\$3) with data ) and		
l		(cop\$3 or transfer\$3) with cell		> 4
-	14	716/11 and (opc or optical near process	USPAT;	2004/05/10 18:17
ĺ		near correction) and photolithography and	US-PGPUB;	=====================================
		mask	EPO; JPO;	
			DERWENT;	*
•		•		
_	160	716/19 and (opc or optical near process	IBM_TDB	2004/05/10 10 15
	100	near correction) and photolithography and	USPAT;	2004/05/10 18:17
			US-PGPUB;	
		mask	EPO; JPO;	
7	1	•	DERWENT;	
. 19			IBM TDB	